



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

re application of

Toshiaki AOAI, et al.

Appln. No.: 09/620,708

Attorney Docket No.: Q60206

Confirmation No.: Not Assigned

Group Art Unit: 1752

Filed: July 20, 2000

Examiner: J. Chu

For: POSITIVE PHOTORESIST COMPOSITION FOR FAR ULTRAVIOLET
EXPOSURE

AMENDMENT UNDER 37 C.F.R. § 1.111

Commissioner for Patents
Washington, D.C. 20231

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FEB 08 2002

TC 1700

Sir:

This Amendment is submitted in response to the Office Action dated October 3, 2001. A Petition for a one-month extension of time is being concurrently filed, making a response due on or before February 4, 2002 (February 3, 2002 being a Sunday). Please amend the above-identified application as follows:

IN THE CLAIMS:

Please enter the following amended claims:

1 (Amended). A positive photoresist composition comprising:

(A) a compound capable of generating an acid upon irradiation with actinic rays or radiation and